

## ABSTRACT

Exposure-An exposure apparatus EX-exposes a substrate P through a liquid LQ-liquid.

The exposure apparatus is provided with a substrate stage PST which can hold the substrate P,substrate, an interferometer system (43),system, which projects a measuring light on a reflecting plane formed on a moving mirror on the substrate stage PST,stage, receives the reflected light and measures position information of the substrate stage PST,stage, and a memory MR Y,memory, which stores error,error information of the reflecting plane under the condition where the liquid is supplied on the substrate stage as first information. The measurement process using the interferometer system and exposure are performed at high accuracy in the immersion exposure area.